

SHIGA7.016APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant | : Hada et al. |
| Int'l Appl. No. | : PCT/JP2003/015347 |
| Int'l Filing Date | : December 1, 2003 |
| For | : METHOD OF FORMING RESIST PATTERN, POSITIVE RESIST COMPOSITION, AND LAYERED PRODUCT |
| Examiner | : Unknown |
| Group Art Unit | : Unknown |

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination on the merits, please amend the present application.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.